

REMARKS**Summary of the Final Office Action**

Claims 24, 26 and 27 stand rejected under 35 U.S.C. § 112, first paragraph, as failing to comply with the written description requirement.

Claims 21-23 and 28 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Miura et al. (U.S. Patent Application No. 2003/0087129) (hereinafter “Miura”) in view of Nishiki et al. (U.S. Patent No. 6,261,144) (hereinafter “Nishiki”).

Claims 21-23, 25 and 28 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Komada (U.S. Patent No. 2001/0038894) (hereinafter “Komada”) in view of Fumihiro (JP 11-335820) (hereinafter “Fumihiro”).

Claims 24-27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Miura in view of Nishiki, as applied to claim 21, and further in view of the allegedly “admitted prior art.”

Claims 26 and 27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Miura in view of Nishiki, as applied to claim 21, and further in view of Konishi et al. (U.S. Patent No. 5,957,743) (hereinafter “Konishi”).

Claims 24, 26 and 27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Komada in view of Fumihiro, as applied to claim 21 above, and further in view of Konishi for substantially the same reasons as applied to claims 26 and 27 above.

Claims 24-27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Miura in view of Nishiki, as applied to claim 21, and further in view of Choi et al. (U.S. Patent Application No. 2002/0063525) (hereinafter “Choi”).

Claims 24, 26 and 27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Komada in view of Fumihiro, as applied to claim 21 above, and further in view of Choi for substantially the same reasons as applied to claims 24-27 above.

Summary of the Response to the Office Action

The undersigned would like to thank Examiners Lin and Hendricks for their courtesy and consideration extended during the May 2, 2007 telephone interview. Based on the discussions during that interview, Applicants have further amended claims 21 and 23, and have added new claim 29, to clarify the claimed relationship between the evaporation sources and the display area, in particular. Applicants respectfully submit that this relationship is not taught or suggested by any of the cited references.

Upon entry of this Preliminary Amendment, claims 1-27 and 29 will be pending, with claims 1-20 being withdrawn, and claim 28 being canceled in the April 24, 2007 Amendment.

Rejection under 35 U.S.C. § 112, first paragraph

Claims 24, 26 and 27 stand rejected under 35 U.S.C. § 112, first paragraph, as failing to meet the written description requirement. This rejection is respectfully traversed for the reasons stated in the Remarks of the April 24, 2007 Amendment. Accordingly, the Examiner is respectfully requested to withdraw this rejection.

Rejections under 35 U.S.C. § 102(e) and 103(a)

Claims 21-23 and 28 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over

Miura in view of Nishiki. Claims 21-23, 25 and 28 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Komada in view of Fumihiro. Claims 24-27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Miura in view of Nishiki, as applied to claim 21, and further in view of the allegedly “admitted prior art.” Claims 26 and 27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Miura in view of Nishiki, as applied to claim 21, and further in view of Konishi. Claims 24, 26 and 27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Komada in view of Fumihiro, as applied to claim 21 above, and further in view of Konishi for substantially the same reasons as applied to claims 26 and 27 above. Claims 24-27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Miura in view of Nishiki, as applied to claim 21, and further in view of Choi. Claims 24, 26 and 27 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Komada in view of Fumihiro, as applied to claim 21 above, and further in view of Choi for substantially the same reasons as applied to claims 24-27 above.

Applicants have further amended claims 21 and 23, and have added new claim 29, to clarify features of the claimed embodiments and/or to improve the form of the claims. Claim 28 was canceled. To the extent that these rejections might be deemed to apply to the claims as newly-amended, they are respectfully traversed for at least the following reasons.

Specifically, as discussed in the Remarks of the April 24, 2007 Amendment, and during the telephone interview, independent claim 21 recites a method of fabricating a plasma display panel having a display area, including the step of forming a protection film on a substrate of the plasma display panel and covering the display area. This step includes (a) feeding the substrate

in a vacuum atmosphere so as to move along a first direction, and (b) heating and evaporating a plurality of evaporation sources positioned to face the substrate.

Claim 21 further recites that when the substrate moves along the first direction and passes the evaporation sources, the display area passes within a space that is defined between a pair of flat planes that extend substantially perpendicular to the first direction from the opposite edges of the display area, and at least one of the evaporation sources is positioned outside the space. An example of this arrangement is shown in FIGs. 2 and 3 of the present application, with the claimed “first direction” reading on first direction 4 and the “pair of flat planes” reading on the planes extending upward from edges 6a of the display area 6, as shown in FIG. 3. New claim 29 further defines the relationship between the evaporation sources and the display area as shown in FIGs. 2 and 3 of the present application. As discussed in the Remarks of the April 24, 2007 Amendment, with this arrangement, a protection film having uniform crystal alignment can be formed over the entire surface of the display area, thereby improving the characteristics of the protection film, such as secondary electron emission and resistance against sputtering.

As further discussed in the Remarks of the April 24, 2007 Amendment and during the telephone interview, Miura discloses an apparatus for making a thin film, in which the thin film is formed on a substrate 12. In the arrangement shown in FIG. 1 of Miura, the substrate 12 is spun by spinning means 21, and the evaporation sources 14a and 14b of the apparatus are positioned somewhere below the substrate 12. However, Applicants respectfully submit that Miura fails to disclose an arrangement in which at least one of the evaporation sources 14a and 14b is positioned outside a space in which the display area passes as explicitly recited in amended independent claim 21.

As discussed in the Remarks of the April 24, 2007 Amendment, Komada discloses an ion plating method in which a substrate 50 is displaced by winding means, and silicon oxide evaporated from a heath 306 is deposited on the substrate 50. The heath 306 is positioned somewhere below the substrate 50. However, Komada also fails to disclose an arrangement in which the heath 306 is positioned outside a space in which the display area passes, as defined in independent claim 21.

Applicants further submit that none of the other cited references make up for the deficiencies in Miura and Komada as discussed above. Accordingly, Applicants respectfully submit that one skilled in the art would not have found the embodiment of the present invention as defined in independent claim 21 obvious in view of Miura, Komada and the secondary references. Furthermore, Applicants respectfully submit that dependent claims 22-27 and 29 are allowable at least because of their dependence from newly-amended independent claim 21, and the reasons set forth above.

CONCLUSION

In view of the foregoing discussion, Applicants respectfully request the entry of the amendments to place the application in clear condition for allowance or, in the alternative, in better form for appeal. Should the Examiner feel that there are any issues outstanding after consideration of this response, the Examiner is invited to contact Applicants' undersigned representative to expedite prosecution. A favorable action is awaited.

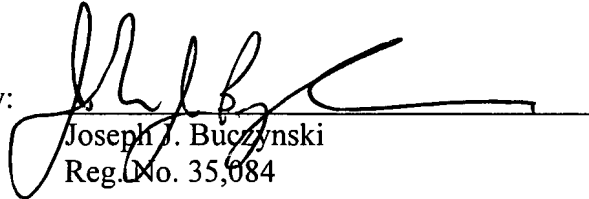
EXCEPT for issue fees payable under 37 C.F.R. § 1.18, the Commissioner is hereby authorized by this paper to charge any additional fees during the entire pendency of this application including fees due under 37 C.F.R. § 1.16 and 1.17 which may be required, including any required extension of time fees, or credit any overpayment to Deposit Account No. 50-0573. This paragraph is intended to be a **CONSTRUCTIVE PETITION FOR EXTENSION OF TIME** in accordance with 37 C.F.R. § 1.136(a)(3).

Respectfully submitted,

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